

ABSTRACT

**EXPOSURE METHOD, EXPOSURE APPARATUS,
METHOD FOR PRODUCING EXPOSURE APPARATUS, AND
METHOD FOR PRODUCING DEVICE**

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In order to produce an exposure apparatus, a frame mechanism is assembled with a base plate, a column, and a support plate. After that, a sub-chamber provided with an illumination system is installed, and a projection optical system PL is placed on the support plate. Concurrently with this operation, a reticle chamber and a reticle stage system are assembled and adjusted, and a wafer chamber and a wafer stage system are assembled and adjusted. The reticle chamber and the wafer chamber are incorporated into the frame mechanism on which the projection optical system is carried. Piping and other components for supplying the purge gas for transmitting an exposure light beam therethrough are arranged at the inside of the reticle chamber and the wafer chamber. The space between the projection optical system and the wafer chamber is tightly closed with a film-shaped soft shield member having flexibility.

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(Figure 1)



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